

Sheet 1 of 1

Form PTO-1449 <div>INFORMATION DISCLOSURE CITATION IN AN APPLICATION (Us approval shows if necessary) MAR 29 2004 U.S. PATENT & TRADEMARK OFFICE</div>	Document Number (Optional) TSmc-03-305	Application Number 10/764,913
	Applicant Bor-Wen Chan et al.	
	Filing Date 01/26/04	Drawn At Unit

U. S. PATENT DOCUMENTS

EXAMINER INITIAL	DOCUMENT NUMBER	DATE	TITLE	CLASS	SUBCLASS	PUBLICATION DATE & APPROXIMATE
ICLI	6500755	12/31/02	Dakshina-Murthy et al.	438	637	12/6/00
	6482726	11/19/02	Aminpur et al.	438	585	10/17/00
	6548423	4/15/03	Plat et al.	438	780	1/16/02
ICLI	6492068	12/10/02	Suzuki	430	5	1/7/00
	6541360	4/11/03	Plat et al.	438	585	4/30/01

FOREIGN PATENT DOCUMENTS

DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
					YES	NO

OTHER DOCUMENTS (Including Author, Title, Date, Portion of Pages, Etc.)

ICLI	U.S. Patent Application Publication US 2002/0164543 A1
ICLI	Lin et al., Publication Date 11/7/02, "Bi-layer Photolithographic Process", US Class 430/313, filed 7/2/01.

EXAMINER /Calvin Lee/	DATE CONSIDERED (11/13/2007)
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